

IEUVI Mask Technical Working Group Meeting

Agenda

San Jose, CA, Thursday February 28, 2008

Hilton hotel San Jose

12:30 – 13:00	Lunch served in meeting room	
13:00 – 13:10	Introduction and greetings	K. Orvek, SEMATECH
13:10 – 15:20	Proposed changes P37/P40/P38 SEMI standards	
	Review history, proposed changes/issues Select discussion foils: <i>CTE, bow, flatness, λ definitions</i> <i>flatness plane, chuck stiffness</i>	K. Orvek, SEMATECH J. Zimmerman, ASML R. Engelstad, Univ. Wisconsin
15:20 – 15:35	<i>Coffee/Tea/Desserts BREAK</i>	
15:35 – 16:35	Particle Control for EUV Mask Lifetime	
	Robotics/Vacuum	M. Amemiya, Selete
	Shipping/Storage/Robotics/Vacuum	L. He, SEMATECH
	E-chuck particles: FEM modeling, data	R. Engelstad, Univ. Wisconsin
	E-chuck particles: Data	K. Ota, Selete
16:35 – 17:00	Wrap Up Discussion & Next Meeting	K. Orvek, SEMATECH